

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No.09/536,037
Filing DateMarch 27, 2000
Inventor Weimin (Michael) Li et al.
AssigneeMicron Technology, Inc.
Group Art Unit2822
ExaminerToniae M. Thomas
Attorney's Docket No.MI22-1398
Customer No.....021567
Title: Low k Interlevel Dielectric Layer Fabrication Methods

To: Box RCE
Commissioner for Patents
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT


References -- See Attached Form PTO-1449

This Request for Continued Examination (RCE) Application is being filed in an abundance of caution to ensure consideration of the references listed on the attached form PTO-1449.

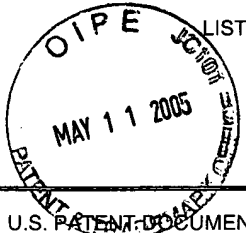
The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No admission is made regarding whether the submitted references are prior art.

Respectfully submitted,

Dated: 11 May 2005

By: 
James E. Lake
Reg. No. 44,854

EV549570593

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1398		SERIAL NO. 09/536,037	
 <p>LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p>				APPLICANT: Li et al.			
				FILING DATE March 27, 2000		GROUP 2822	
U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,121,133	09/19/00	Iyer et al.	438	636	
	AB	6,632,712 B1	07/11/00	Ang et al.	438	212	
	AC	5,711,987	07/05/88	Bearinger et al.	427	7	
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AJ	TW 47112 A	01/01/2002	Taiwan – Abstract			X
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AM		Wolf, S., and Tauber, Richard, Silicon Processing for the VLSI Era; Vol. 1; Process Technology; "Silicon: Single Crystal Growth and Wafer Preparation"; pages 1 and 2				
	AN						
EXAMINER		DATE CONSIDERED					
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>							

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